

Energy Band diagram



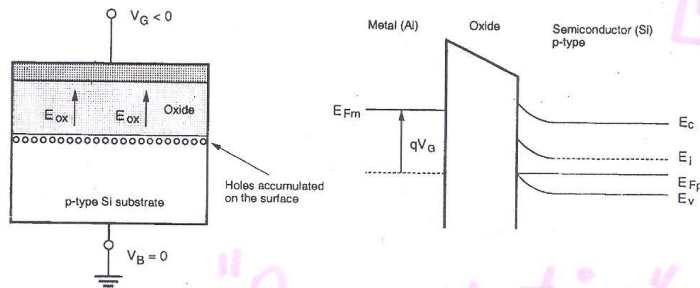
3.2. The MOS System under External Bias

(EBD of MOS under Accumulation, depletion & inversion)

We now turn our attention to the electrical behavior of the MOS structure under externally applied bias voltages. Assume that the substrate voltage is set at $V_B = 0$, and let the gate voltage be the controlling parameter. Depending on the polarity and the magnitude of V_G , three different operating regions can be observed for the MOS system: **accumulation, depletion, and inversion.**

Accumulation:

If a negative voltage V_G is applied to the gate electrode, the holes in the p-type substrate are attracted to the semiconductor-oxide interface. The majority carrier concentration near the surface becomes larger than the equilibrium hole concentration in the substrate; hence, this condition is called **carrier accumulation** on the surface (Fig. 3.5). Note that in this case, the oxide electric field is directed towards the gate electrode. The negative surface potential also causes the energy bands to bend upward near the surface. While the hole density near the surface increases as a result of the applied negative gate bias, the electron (minority carrier) concentration decreases as the negatively charged electrons are pushed deeper into the substrate.



[Band bend upwards for $-V_G$]

"Accumulation"

Figure 3.5. The cross-sectional view and the energy band diagram of the MOS structure operating in accumulation region.

Depletion:

Now consider the next case in which a small positive gate bias V_G is applied to the gate electrode. Since the substrate bias is zero, the oxide electric field will be directed towards the substrate in this case. The positive surface potential causes the energy bands to bend downward near the surface, as shown in Fig. 3.6. The majority carriers, i.e., the holes in the substrate, will be repelled back into the substrate as a result of the positive gate bias, and these holes will leave negatively charged fixed acceptor ions behind. Thus, a **depletion** region is created near the surface. Note that under this bias condition, the region near the semiconductor-oxide interface is nearly devoid of all mobile carriers.

The thickness x_d of this depletion region on the surface can easily be found as a function of the surface potential ϕ_s . Assume that the mobile hole charge in a thin horizontal layer parallel to the surface is

Derivation for x_d :

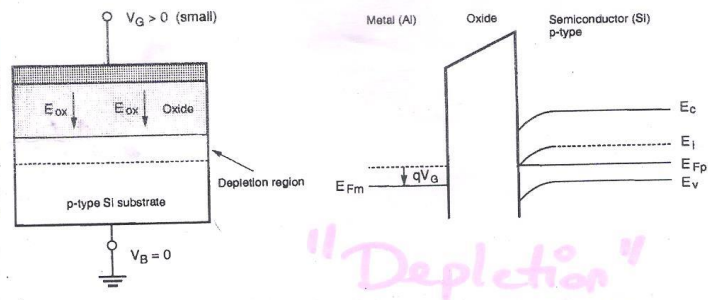


Figure 3.6. The cross-sectional view and the energy band diagram of the MOS structure operating in depletion mode, under small gate bias.

$$dQ = -q \cdot N_A \cdot dx \quad (3.7)$$

The change in surface potential required to displace this charge sheet dQ by a distance x_d away from the surface can be found by using the Poisson equation.

$$d\phi_s = -x \cdot \frac{dQ}{\epsilon_{Si}} = \frac{q \cdot N_A \cdot x}{\epsilon_{Si}} dx \quad (3.8)$$

Integrating (3.7) along the vertical dimension (perpendicular to the surface) yields

$$\int_{\phi_F}^{\phi_s} d\phi_s = \int_0^{x_d} \frac{q \cdot N_A \cdot x}{\epsilon_{Si}} dx \quad (3.9)$$

$$\phi_s - \phi_F = \frac{q \cdot N_A \cdot x_d^2}{2 \epsilon_{Si}} \quad (3.10)$$

Thus, the depth of the depletion region is

$$x_d = \sqrt{\frac{2 \epsilon_{Si} \cdot |\phi_s - \phi_F|}{q \cdot N_A}} \quad \text{cm} \quad (3.11)$$

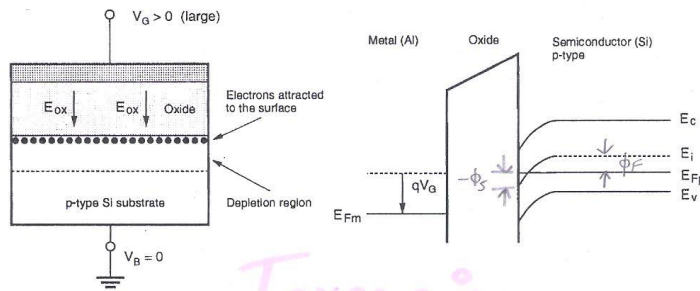
and the depletion region charge density, which consists solely of fixed acceptor ions in this region, is given by the following expression

$$Q = -q \cdot N_A \cdot x_d = -\sqrt{2q \cdot N_A \cdot \epsilon_{Si} \cdot |\phi_s - \phi_F|} \quad (3.12)$$

Inversion:

The amount of this depletion region charge plays a very important role in the analysis of threshold voltage, as we will examine shortly.

To complete our qualitative overview of different bias conditions and their effects upon the MOS system, consider next a further increase in the positive gate bias. As a result of the increasing surface potential, the downward bending of the energy bands will increase as well. Eventually, the mid-gap energy level E_i becomes smaller than the Fermi level E_{Fp} on the surface, which means that the substrate semiconductor in this region becomes n-type. Within this thin layer, the electron density is larger than the majority hole density, since the positive gate potential attracts additional minority carriers (electrons) from the bulk substrate to the surface (Fig. 3.7). The n-type region created near the surface by the positive gate bias is called the *inversion layer*, and this condition is called *surface inversion*. It will be seen that the thin inversion layer on the surface with a large mobile electron concentration can be utilized for conducting current between two terminals of the MOS transistor.



Inversion

Figure 3.7. The cross-sectional view and the energy band diagram of the MOS structure in surface inversion, under larger gate bias voltage.

"
Inversion
condition"
 $\phi_s = -\phi_F$

As a practical definition, the surface is said to be *inverted* when the density of mobile electrons on the surface becomes equal to the density of holes in the bulk (p-type) substrate. This condition requires that the surface potential has the same magnitude, but the reverse polarity, as the bulk Fermi potential ϕ_F . Once the surface is inverted, any further increase in the gate voltage leads to an increase of mobile electron concentration on the surface, but not to an increase of the depletion depth. Thus, the depletion region depth achieved at the onset of surface inversion is also equal to the maximum depletion depth, x_{dm} , which remains constant for higher gate voltages. Using the inversion condition $\phi_s = -\phi_F$, the maximum depletion region depth at the onset of surface inversion can be found from (3.11) as follows:

$$x_{dm} = \sqrt{\frac{2\epsilon_{Si} |2\phi_F|}{qN_A}}$$